

A Model for Charge Transport in Randomly-Ordered Carbon Nanoclusters Demonstration of a rudimentary carbon based sensor



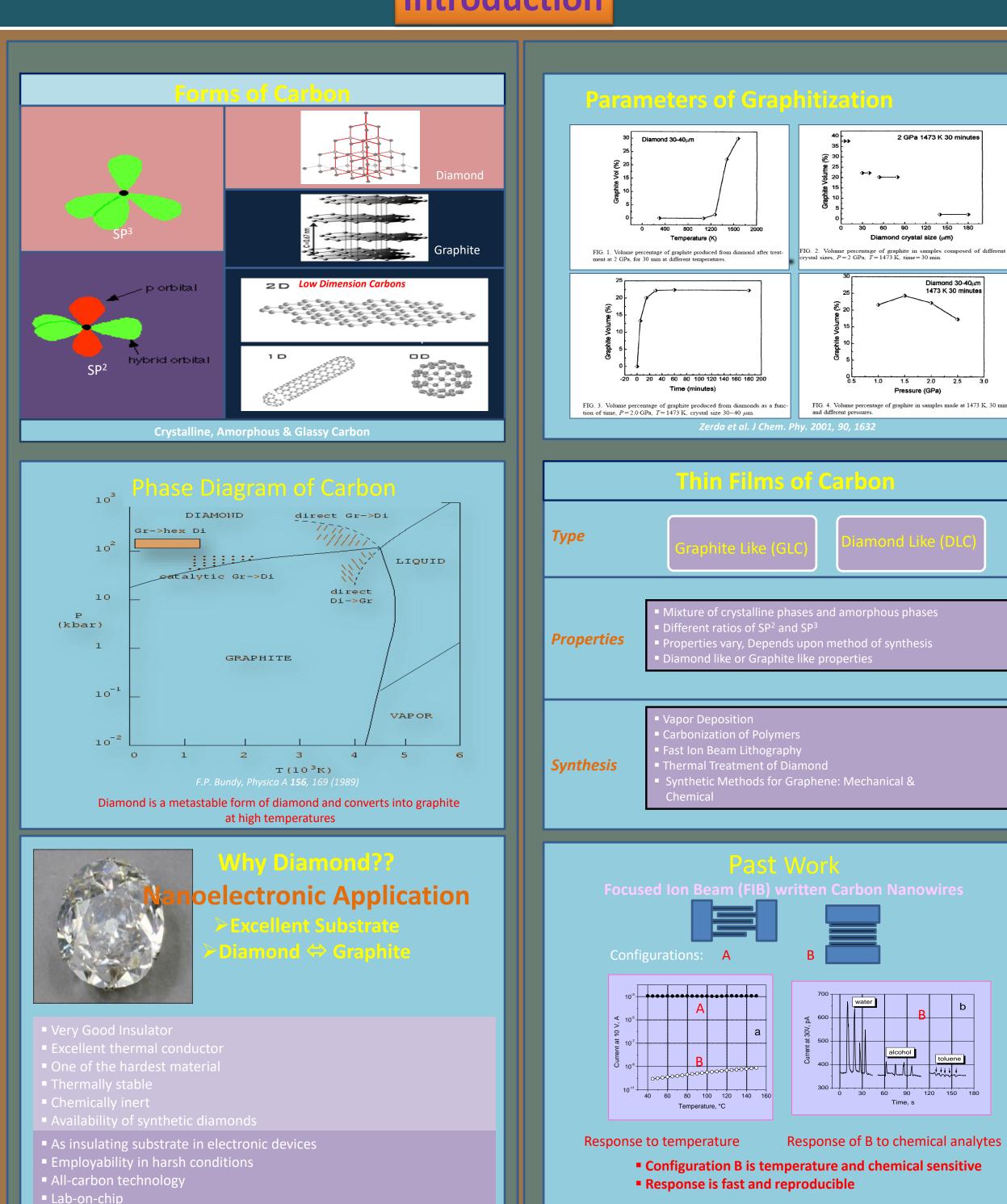
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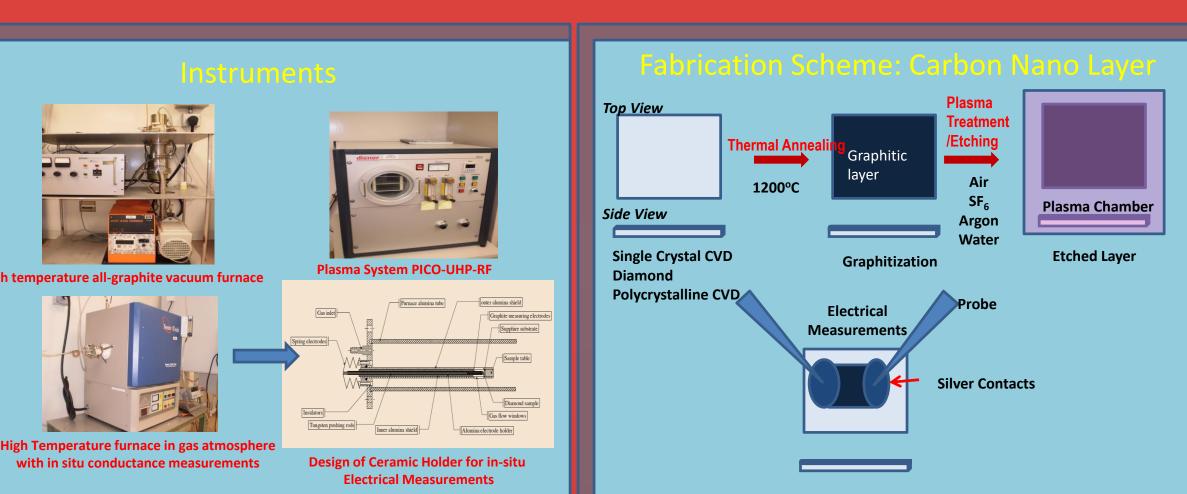
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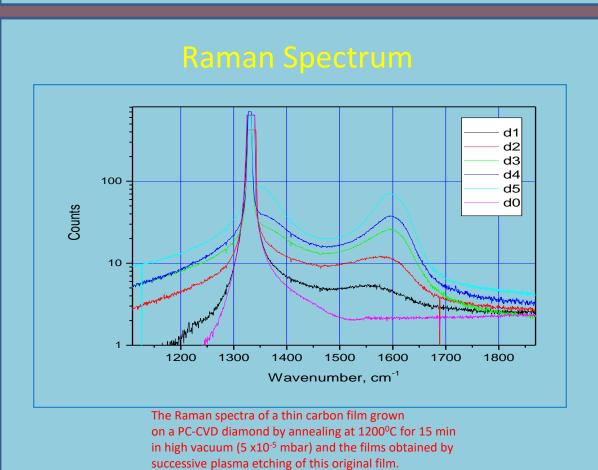
Abstract

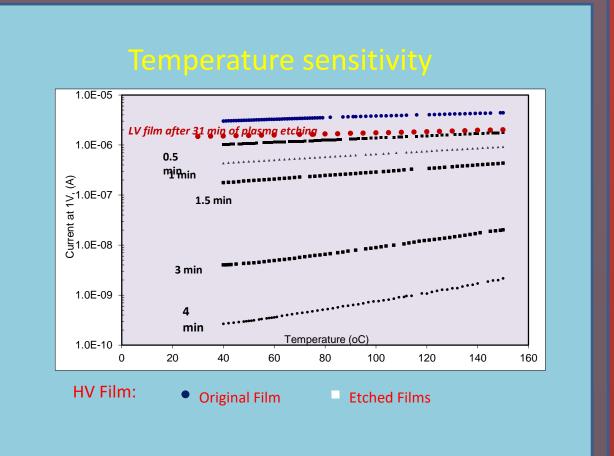
The carbon nanofilms on diamond were obtained by irreversible graphitization of diamond at above 1000 0C. The exposure to plasma reduces the surface conductance of the carbon nanofilms on diamond as result of a partial removal of carbon and the plasma-stimulated amorphization. The experimentally observed exponential dependence of conductance G of the carbon nanofilms on temperature T can be well represented by a relation G = A exp (BT). This behavior is explained by a model based on the thermally vibrating energy barriers formed between the carbon nanoclusters constituting the thin carbon nanofilms. The empirical constants A and B relate to the density of the carbon nanoclusters and the energy barrier height between them respectively. A rudimentary temperature and chemical sensor is demonstrated utilizing the electronic properties of resultant carbon system.

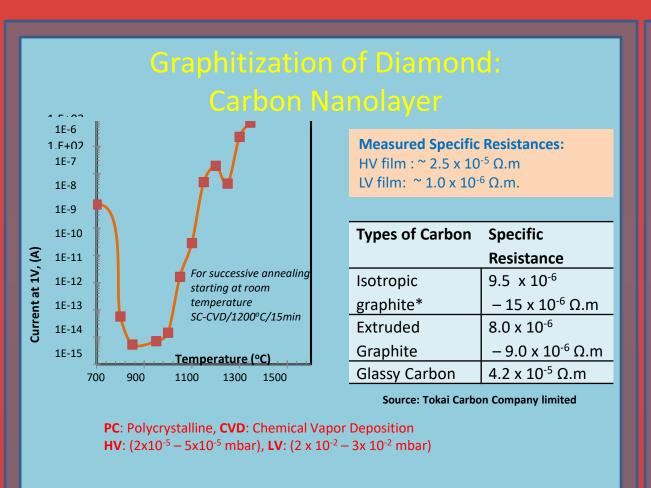
Introduction

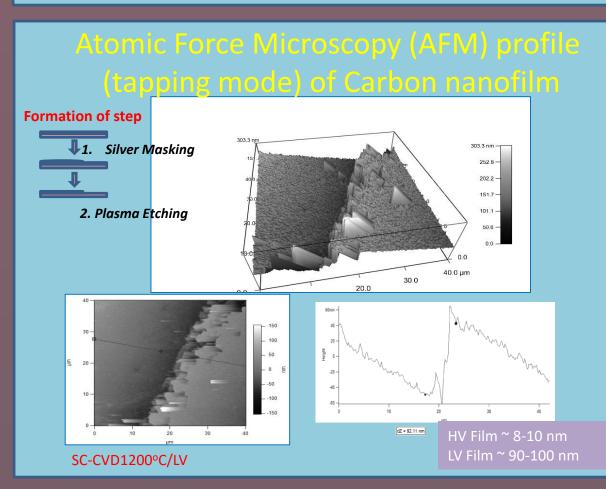


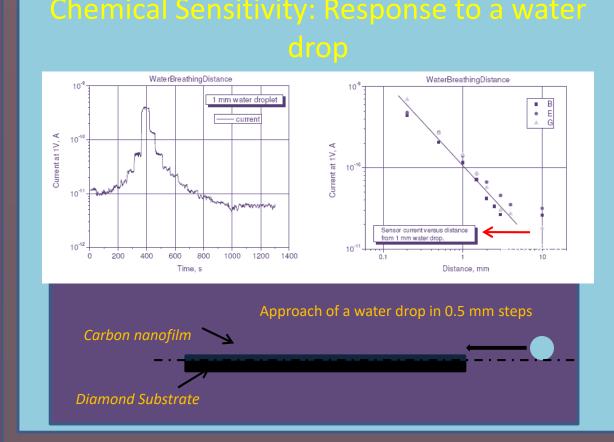


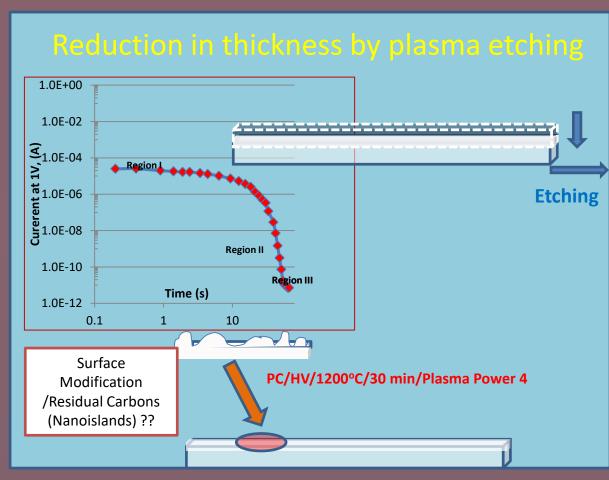


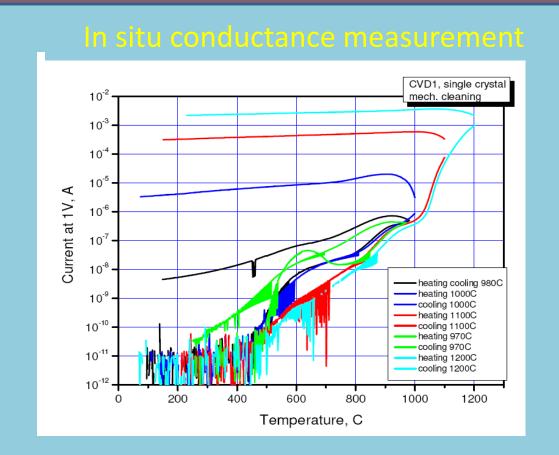


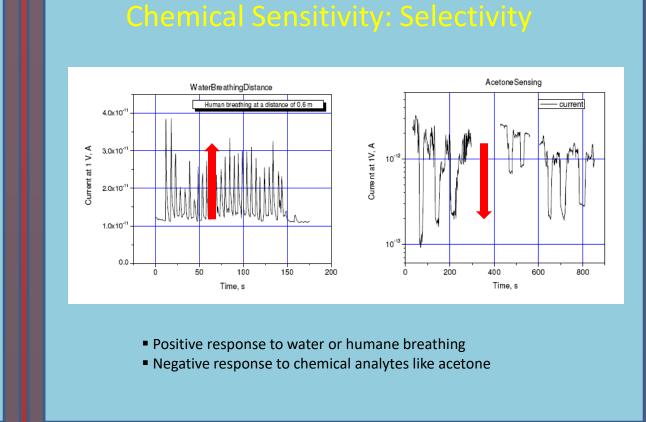












Conclusions

- > The temperature and chemical sensitive few carbon atoms thin films of carbon can be obtained by thermal annealing of diamond films at high temperatures (higher than 1000°C) combined with plasma etching.
- > The grown films are amorphous in nature with short range graphitic

(a) Thick films grown in low vacuum at 1200°C for 30 min:

as-grown and after 5 minute plasma etching in air plasma (b) Thick films grown in Ar atmosphere at 1000°C for 10 min:

as grown and exposed to water vapor of different densities

- > The thin film obtained in high vacuum (5 x 10⁻⁵ mbar) is about 12 nm thick; while a thick film obtained in relatively low vacuum (2×10^{-2} mbar) is about 95 nm.
- > The thickness of the thick LV film can be easily reduced to few nm by prolonged plasma etching to give a thin temperature sensitive film.
- Characterization techniques like X- Ray photoelectron spectroscopy (XPS) and X-Ray diffraction measurements (XRD) may give more insight into the material structure of these nano films. Besides, the role of pressure, temperature and annealing time needs to be investigated in more detail.
- > Thus, we have an all carbon based technology to grow nano films of carbon for nano temperature and chemical sensor application.

References

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